

SPUTTERING TARGET FOR FORMING MAGNETIC RECORDING FILM
AND METHOD FOR PRODUCING SAME

ABSTRACT

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A C-containing FePt-based sputtering target for forming a magnetic recording film, wherein an average thickness of an Fe-Pt alloy phase in a polished surface of a cross section vertical to a sputtering surface is 10 μm or more. An object of this invention is to provide a ferromagnetic material sputtering target capable of suppressing the generation of particles caused by an abnormal discharge during sputtering.

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Fig. 1